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**D2S EXPANDS MANAGEMENT TEAM WITH PHOTOMASK AND SEMICONDUCTOR
INDUSTRY VETERANS**

***New Hires from Intel, KLA-Tencor and Synopsys
Bring Wealth of Semiconductor Experience as D2S Enters Next Stage of Growth***

SAN JOSE, Calif., February 13, 2012—D2S®, a supplier of computational design platforms, today announced that it has bolstered its management team with the hiring of three semiconductor industry veterans with deep business and technology expertise in electron beam (eBeam), photomask and lithography technology. Sterling Watson has joined D2S as vice president of engineering, Anthony Adamov has joined the company as vice president of business development, and Ryan Pearman has become the company's director of modeling.

"We are pleased to welcome Sterling, Anthony and Ryan to D2S," stated Aki Fujimura, CEO of D2S. "They bring a wealth and diversity of knowledge from their previous roles at leading companies in semiconductor design, photomask and lithography process technology. This will prove invaluable to D2S as we grow our infrastructure to support innovative eBeam technologies, such as our model-based mask data preparation (MB-MDP) offerings, to improve mask accuracy and write-times at the 20-nm design node and beyond."

Prior to joining D2S, Watson was chief technology supply officer at KLA-Tencor. During his 18-year career at KLA-Tencor he held multiple management roles, including general manager of Electron Beam Review and vice president of engineering for the Reticle and Photomask Inspection Division (RAPID). Before joining KLA-Tencor, he worked for ETEC Systems (since acquired by Applied Materials) developing eBeam mask data preparation software systems. Watson holds a bachelor's degree in physics from Stanford University and a doctorate in physics from the University of California at Santa Cruz.

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Adamov joined D2S with Stanford Robotics, a mask optimization company he co-founded and led as CEO. Prior to that, he headed the Inverse Lithography Division of Luminescent Technology as general manager and vice president of business development for the company. Earlier, he worked in various engineering and management functions at Synopsys, including global application manager. Adamov earned a doctorate in theoretical physics from Tufts University.

Pearman joined D2S after spending eight years at Intel where he was responsible for fine-tuning critical production models, developing next-generation lithography modeling capabilities, and studying the effects of mask errors on the patterning process. He earned a doctorate in physical chemistry from the University of Illinois, and previously held a postdoctoral position at Columbia University.

About D2S, Inc.

D2S is a supplier of a computational design platform to maximize existing eBeam technology to reduce mask costs for both low- and high-volume applications. D2S advanced design-for-eBeam (DFeB) mask solution reduces mask write times for high-volume designs with complex and circular features using existing eBeam mask writing equipment. D2S DFeB direct write solution virtually eliminates the costs of masks for low-volume applications and can speed time-to-market by shortening the design-to-lithography process flow. D2S is the managing sponsor of the eBeam Initiative. Headquartered in San Jose, Calif., the company was founded in 2007. For more information, see: www.design2silicon.com.

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